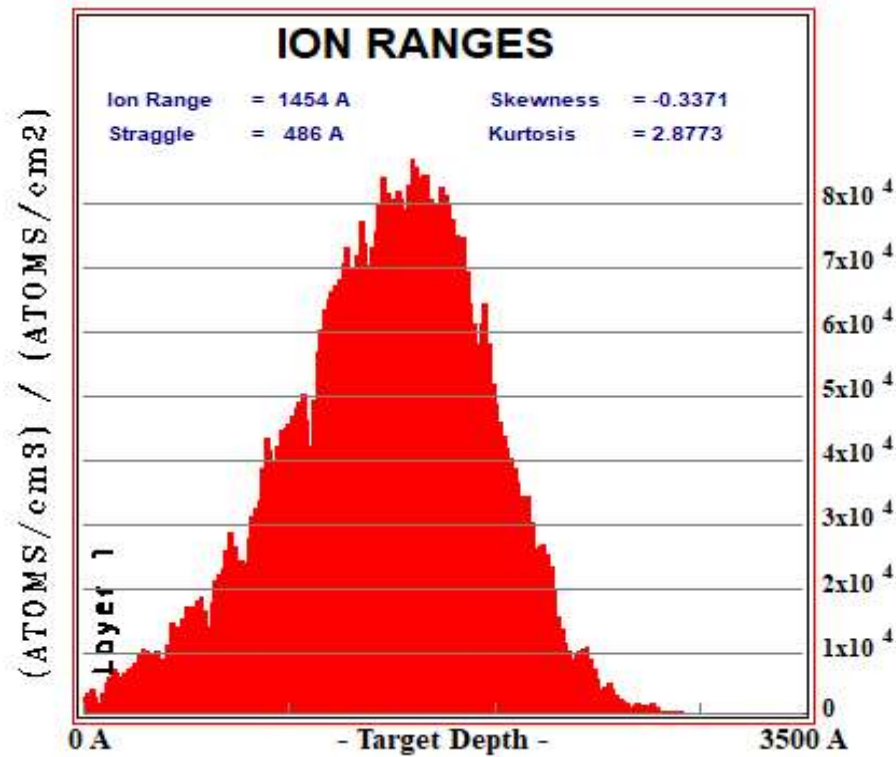


## Boron in Silicon implant



## 9999 Ions Calculated

Ion Type = B  
Ion Energy = 40 keV  
Ion Angle = 0

SRIM-2008.04  
October 27, 2024  
www.SRIM.org

## Calculation Parameters:

Backscattered Ions 80  
Transmitted Ions 1  
Vacancies/Ion 299.5

**ION STATS**

	Range	Straggle
Longitudinal	1454 A	486 A
Lateral Proj.	443 A	551 A
Radial	691 A	345 A

**Type of Damage Calculation**  
Quick: Kinchin-Pease

**Stopping Power Version**  
SRIM-2008

% ENERGY	LOSS Ions	Recoils
Ionization	63.07	7.97
Vacancies	0.25	1.24
Phonons	0.87	26.60

## SPUTTERING YIELD

	Atoms/ion	eV/Atom
TOTAL		
Si	0.000000	0.00

## Target layers:

	Layer Name	Width (A)	Density	Si (28.086)	Solid/Gas	Stop Corr.
1	Layer 1	3000	2.321	1.00000	Solid	1
	Lattice Binding Energy			2		
	Surface Binding Energy			4.7		
	Displacement Energy			15		